

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	258	polysiloxan\$ and (hexamethoxymethylmelamine or cymel near5 "303") and (photoa\$ photob\$ photoc\$ photod\$ photoe\$ photof\$ photog\$ photoh\$ photoi\$ photoj\$ photok\$ photol\$ photom\$ photon\$ photoo\$ photop\$ photoq\$ photor\$ photos\$ photot\$ photou\$ photov\$ photow\$ photoX\$ photoY\$ photoZ\$ photo)	US-PGPUB; USPAT	OR	OFF	2008/01/10 08:38
S2	170	polysiloxan\$ and (hexamethoxymethylmelamine or cymel near5 "303") and (photoa\$ photob\$ photoc\$ photod\$ photoe\$ photof\$ photog\$ photoh\$ photoi\$ photoj\$ photok\$ photol\$ photom\$ photon\$ photoo\$ photop\$ photoq\$ photor\$ photos\$ photot\$ photou\$ photov\$ photow\$ photoX\$ photoY\$ photoZ\$ photo) and (fluorinated perfluorinated perfluoroalkyl fluorine)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/01/10 08:39
S3	241	(polysiloxan\$ siloxane dimethylsiloxane) and (hexamethoxymethylmelamine or cymel near5 "303") and (photoa\$ photob\$ photoc\$ photod\$ photoe\$ photof\$ photog\$ photoh\$ photoi\$ photoj\$ photok\$ photol\$ photom\$ photon\$ photoo\$ photop\$ photoq\$ photor\$ photos\$ photot\$ photou\$ photov\$ photow\$ photoX\$ photoY\$ photoZ\$ photo) and (fluorinated perfluorinated perfluoroalkyl fluorine)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/01/10 09:47
S4	242	(polysiloxan\$ siloxane dimethylsiloxane) and (hexamethoxymethylmelamine or cymel near5 "303") and (photoa\$ photob\$ photoc\$ photod\$ photoe\$ photof\$ photog\$ photoh\$ photoi\$ photoj\$ photok\$ photol\$ photom\$ photon\$ photoo\$ photop\$ photoq\$ photor\$ photos\$ photot\$ photou\$ photov\$ photow\$ photoX\$ photoY\$ photoZ\$ photo) and (fluorinated perfluorinated perfluoroalkyl fluorine fluoroalkyl)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/01/10 09:56
S5	1	S4 not S3	US-PGPUB; USPAT	OR	OFF	2008/01/10 09:56
S6	35	MERAMINE	US-PGPUB; USPAT	OR	OFF	2008/01/10 11:02
S7	2	("6440632").PN.	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/01/10 11:08
S8	1	1999-458055.NRAN.	DERWENT	OR	OFF	2008/01/10 11:08
S9	39	vps adj "1001"	US-PGPUB; USPAT	OR	OFF	2008/01/10 11:52
S10	1	(US-6271326-\$).did.	USPAT	OR	OFF	2008/01/10 11:57
S11	2	(US-6271326-\$).did.	USPAT; DERWENT	OR	OFF	2008/01/10 11:57
S12	1	(US-20030129931-\$).did.	US-PGPUB	OR	OFF	2008/01/10 14:02
S13	2	(US-20030129931-\$).did.	US-PGPUB; DERWENT	OR	OFF	2008/01/10 14:02
S14	1	("6221498").PN.	US-PGPUB; USPAT	OR	OFF	2008/01/11 10:16

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	1	("5958648").PN.	US-PGPUB; USPAT	OR	OFF	2008/01/08 11:52
S2	6	(("6214416") or ("6335061") or ("6440569") or ("6485838") or ("6660394") or ("6737169")).PN.	US-PGPUB; USPAT	OR	OFF	2008/01/08 11:52
S3	10136	((430/270.1,280.1,325) or (522/126) or (427/508,510,515,517,518)).CCLS.	US-PGPUB; USPAT	OR	OFF	2008/01/08 15:39
S4	35	S3 and (antifoul\$ anti adj foul\$)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/01/08 12:12
S5	1	("20030207202").PN.	US-PGPUB; USPAT	OR	OFF	2008/01/08 13:30
S6	2	("20030207202").PN.	US-PGPUB; USPAT; DERWENT	OR	OFF	2008/01/08 15:10
S7	0	jp-2001089625-\$ did.	US-PGPUB; USPAT	OR	OFF	2008/01/09 11:05
S8	2	jp-2001089625-\$ did.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/01/08 15:19
S9	2	jp-2002090996-\$ did.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/01/08 15:21
S10	2	jp-09054432-\$ did.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/01/08 15:28
S11	2	jp-2002040659-\$ did.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/01/08 15:30
S12	2	jp-2003035961-\$ did.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/01/09 15:33

EAST Search History

S13	2	jp-2003262959-.did.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/01/08 15:32
S14	1	S9 and (photoa\$ photob\$ photoc\$ photod\$ photoe\$ photof\$ photog\$ photoh\$ photoi\$ photoj\$ photok\$ photol\$ photom\$ photon\$ photoo\$ photop\$ photoq\$ photor\$ photos\$ photot\$ photou\$ photov\$ photow\$ photoX\$ photoY\$ photoZ\$ photo)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/01/08 15:41
S15	10136	((430/270.1,280.1,325) or (522/126) or (427/508,510,515,517,518)).CCLS.	US-PGPUB; USPAT	OR	OFF	2008/01/08 15:41
S16	9136	(photoa\$ photob\$ photoc\$ photod\$ photoe\$ photof\$ photog\$ photoh\$ photoi\$ photoj\$ photok\$ photol\$ photom\$ photon\$ photoo\$ photop\$ photoq\$ photor\$ photos\$ photot\$ photou\$ photov\$ photow\$ photoX\$ photoY\$ photoZ\$ photo) and S15	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/01/08 15:45
S17	74	(photoa\$ photob\$ photoc\$ photod\$ photoe\$ photof\$ photog\$ photoh\$ photoi\$ photoj\$ photok\$ photol\$ photom\$ photon\$ photoo\$ photop\$ photoq\$ photor\$ photos\$ photot\$ photou\$ photov\$ photow\$ photoX\$ photoY\$ photoZ\$ photo) and S15 and hexamethylolmelamine	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/01/08 18:07
S18	21	(photoa\$ photob\$ photoc\$ photod\$ photoe\$ photof\$ photog\$ photoh\$ photoi\$ photoj\$ photok\$ photol\$ photom\$ photon\$ photoo\$ photop\$ photoq\$ photor\$ photos\$ photot\$ photou\$ photov\$ photow\$ photoX\$ photoY\$ photoZ\$ photo) and S15 and hexamethylolmelamine and (fluoro perfluoro fluorina\$)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/01/08 16:24
S19	1	("6165684").PN.	US-PGPUB; USPAT	OR	OFF	2008/01/08 16:24
S20	53	(photoa\$ photob\$ photoc\$ photod\$ photoe\$ photof\$ photog\$ photoh\$ photoi\$ photoj\$ photok\$ photol\$ photom\$ photon\$ photoo\$ photop\$ photoq\$ photor\$ photos\$ photot\$ photou\$ photov\$ photow\$ photoX\$ photoY\$ photoZ\$ photo) and S15 and hexamethylolmelamine not S18	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/01/08 16:53
S21	0	(photoa\$ photob\$ photoc\$ photod\$ photoe\$ photof\$ photog\$ photoh\$ photoi\$ photoj\$ photok\$ photol\$ photom\$ photon\$ photoo\$ photop\$ photoq\$ photor\$ photos\$ photot\$ photou\$ photov\$ photow\$ photoX\$ photoY\$ photoZ\$ photo) and S15 and metholated	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/01/08 18:08
S22	37	metholated	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/01/08 18:10

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S23	3826	methylolated	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/01/08 18:10
S24	83	methylolated and S15	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/01/08 18:10
S28	2	jp-10025388-\$ did.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/01/09 11:06
S29	69114	vinyl adj monomer	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/01/09 14:07
S30	1616	vinyl adj monomer same norbornene	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/01/09 14:07
S31	1046	vinyl adj monomer with norbornene	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/01/09 14:12
S32	15	vinyl adj monomer with norbornene and 430/270.1.ccls.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/01/09 14:08
S33	165	vinyl adj monomer near10 norbornene	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/01/09 14:12
S35	530	nishikawa.inv. with akira.inv.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/01/09 15:35

EAST Search History

S36	8	nishikawa.inv. with akira.inv. and watanabe.inv. with fusaka.inv.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/01/09 15:36
S37	10136	((430/270.1,280.1,325) or (522/126) or (427/508,510,515,517,518)).CCLS.	US-PGPUB; USPAT	OR	OFF	2008/01/09 16:32
S38	1251	S37 and siloxan\$	US-PGPUB; USPAT	OR	OFF	2008/01/09 16:43
S39	1026	S37 and polysiloxan\$	US-PGPUB; USPAT	OR	OFF	2008/01/09 16:52
S40	1835	S38 S39	US-PGPUB; USPAT	OR	OFF	2008/01/09 16:44
S41	1756	(S38 S39) and (photoa\$ photob\$ photoc\$ photod\$ photoe\$ photof\$ photog\$ photoh\$ photoi\$ photoj\$ photok\$ photol\$ photom\$ photon\$ photoo\$ photop\$ photoq\$ photor\$ photos\$ photot\$ photou\$ photov\$ photow\$ photoX\$ photoY\$ photoZ\$ photo)	US-PGPUB; USPAT	OR	OFF	2008/01/09 16:44
S42	996	(S38 S39) and (photoa\$ photob\$ photoc\$ photod\$ photoe\$ photof\$ photog\$ photoh\$ photoi\$ photoj\$ photok\$ photol\$ photom\$ photon\$ photoo\$ photop\$ photoq\$ photor\$ photos\$ photot\$ photou\$ photov\$ photow\$ photoX\$ photoY\$ photoZ\$ photo) and (\$crosslink\$)	US-PGPUB; USPAT	OR	OFF	2008/01/09 16:46
S43	286	(S38 S39) and (photoa\$ photob\$ photoc\$ photod\$ photoe\$ photof\$ photog\$ photoh\$ photoi\$ photoj\$ photok\$ photol\$ photom\$ photon\$ photoo\$ photop\$ photoq\$ photor\$ photos\$ photot\$ photou\$ photov\$ photow\$ photoX\$ photoY\$ photoZ\$ photo) and (\$crosslink\$) and (methoxymethyl\$)	US-PGPUB; USPAT	OR	OFF	2008/01/09 16:47
S44	66	(S38 S39) and (photoa\$ photob\$ photoc\$ photod\$ photoe\$ photof\$ photog\$ photoh\$ photoi\$ photoj\$ photok\$ photol\$ photom\$ photon\$ photoo\$ photop\$ photoq\$ photor\$ photos\$ photot\$ photou\$ photov\$ photow\$ photoX\$ photoY\$ photoZ\$ photo) and (\$crosslink\$) and (hexamethoxymethyl\$)	US-PGPUB; USPAT	OR	OFF	2008/01/09 16:48
S45	311	S43 or S44	US-PGPUB; USPAT	OR	OFF	2008/01/09 16:48
S46	2388	polysiloxan\$ with (perfluoro fluorinated fluoropolymer fluoro)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/01/09 16:52
S47	45	polysiloxan\$ with (perfluoro fluorinated fluoropolymer fluoro) and (methoxymethyl or hexamethoxymethyl or hexamethoxymethylmelamine or cymel near5 "303")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/01/09 17:04

EAST Search History

S48	1017	polysiloxan\$ and (methoxymethyl or hexamethoxymethyl or hexamethoxymethylmelamine or cymel near5 "303") and (photoa\$ photob\$ photoc\$ photod\$ photoe\$ photof\$ photog\$ photoh\$ photoi\$ photoj\$ photok\$ photol\$ photom\$ photon\$ photoo\$ photop\$ photoq\$ photor\$ photos\$ photot\$ photou\$ photov\$ photow\$ photoX\$ photoY\$ photoZ\$ photo)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/01/09 17:05
S49	259	polysiloxan\$ and (hexamethoxymethylmelamine or cymel near5 "303") and (photoa\$ photob\$ photoc\$ photod\$ photoe\$ photof\$ photog\$ photoh\$ photoi\$ photoj\$ photok\$ photol\$ photom\$ photon\$ photoo\$ photop\$ photoq\$ photor\$ photos\$ photot\$ photou\$ photov\$ photow\$ photoX\$ photoY\$ photoZ\$ photo)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/01/09 17:06

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11 Jan 2008

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NEWS	2	AUG 06	CAS REGISTRY enhanced with new experimental property tags
NEWS	3	AUG 06	FSTA enhanced with new thesaurus edition
NEWS	4	AUG 13	CA/CAplus enhanced with additional kind codes for granted patents
NEWS	5	AUG 20	CA/CAplus enhanced with CAS indexing in pre-1907 records
NEWS	6	AUG 27	Full-text patent databases enhanced with predefined patent family display formats from INPADOCDB
NEWS	7	AUG 27	USPATOLD now available on STN
NEWS	8	AUG 28	CAS REGISTRY enhanced with additional experimental spectral property data
NEWS	9	SEP 07	STN AnaVist, Version 2.0, now available with Derwent World Patents Index
NEWS	10	SEP 13	FORIS renamed to SOFIS
NEWS	11	SEP 13	INPADOCDB enhanced with monthly SDI frequency
NEWS	12	SEP 17	CA/CAplus enhanced with printed CA page images from 1967-1998
NEWS	13	SEP 17	CAplus coverage extended to include traditional medicine patents
NEWS	14	SEP 24	EMBASE, EMBAL, and LEMBASE reloaded with enhancements
NEWS	15	OCT 02	CA/CAplus enhanced with pre-1907 records from Chemisches Zentralblatt
NEWS	16	OCT 19	BEILSTEIN updated with new compounds
NEWS	17	NOV 15	Derwent Indian patent publication number format enhanced
NEWS	18	NOV 19	WPIX enhanced with XML display format
NEWS	19	NOV 30	ICSD reloaded with enhancements
NEWS	20	DEC 04	LINPADOCDB now available on STN
NEWS	21	DEC 14	BEILSTEIN pricing structure to change
NEWS	22	DEC 17	USPATOLD added to additional database clusters
NEWS	23	DEC 17	IMSDRUGCONF removed from database clusters and STN
NEWS	24	DEC 17	DGENE now includes more than 10 million sequences
NEWS	25	DEC 17	TOXCENTER enhanced with 2008 MeSH vocabulary in MEDLINE segment
NEWS	26	DEC 17	MEDLINE and LMEDLINE updated with 2008 MeSH vocabulary
NEWS	27	DEC 17	CA/CAplus enhanced with new custom IPC display formats
NEWS	28	DEC 17	STN Viewer enhanced with full-text patent content from USPATOLD
NEWS	29	JAN 02	STN pricing information for 2008 now available

NEWS EXPRESS 19 SEPTEMBER 2007: CURRENT WINDOWS VERSION IS V8.2,
CURRENT MACINTOSH VERSION IS V6.0c(ENG) AND V6.0Jc(JP),
AND CURRENT DISCOVER FILE IS DATED 19 SEPTEMBER 2007.

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=> s antifoul? or anti adj foul?
9191 ANTIFOUL?
479840 ANTI
284 ADJ
26178 FOUL?
0 ANTI ADJ FOUL?
(ANTI(W)ADJ(W)FOUL?)
L1 9191 ANTIFOUL? OR ANTI ADJ FOUL?

=> s 11 and photo?
1545419 PHOTO?
L2 463 L1 AND PHOTO?

=> s 12 and (fluoro? or perfluoro? or difluor? or trifluor? or tetrafluor? or pentafluor? or hexafluor? or heptafluor?)
457518 FLUORO?
55846 PERFLUORO?
61908 DIFLUOR?
174987 TRIFLUOR?
89526 TETRAFLUOR?
29091 PENTAFLUOR?
84138 HEXAFLUOR?
7707 HEPTAFLUOR?
L3 72 L2 AND (FLUORO? OR PERFLUORO? OR DIFLUOR? OR TRIFLUOR? OR TETRAFLUOR? OR PENTAFLUOR? OR HEXAFLUOR? OR HEPTAFLUOR?)

=> s l3 and (methy lol? or dimethy lol? or trimethy lol? or tetramethy lol? or polymethy lol?)
 14450 METHY LOL?
 8969 DIMETHY LOL?
 31652 TRIMETHY LOL?
 840 TETRAMETHY LOL?
 307 POLYMETHY LOL?
 L4 1 L3 AND (METHY LOL? OR DIMETHY LOL? OR TRIMETHY LOL? OR TETRAMETHY LOL? OR POLYMETHY LOL?)

=> d all

L4 ANSWER 1 OF 1 CAPLUS COPYRIGHT 2008 ACS on STN
 AN 1998:767816 CAPLUS
 DN 130:67885
 ED Entered STN: 08 Dec 1998
 TI Anticorrosive multilayer coatings for steel structure and their coating method
 IN Nakayama, Shunsuke; Ishida, Noriyuki; Matsuda, Mitsuhiro
 PA Dai Nippon Toryo Co., Ltd., Japan
 SO Jpn. Kokai Tokkyo Koho, 12 pp.
 CODEN: JKXXAF
 DT Patent
 LA Japanese
 IC ICM B01J035-02
 ICS B05D001-38; B05D007-14; B05D007-24
 CC 42-10 (Coatings, Inks, and Related Products)

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 10314596	A	19981202	JP 1997-126153	19970516
	JP 3260097	B2	20020225		
PRAI	JP 1997-126153		19970516		

CLASS

	PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
	JP 10314596	ICM	B01J035-02
		ICS	B05D001-38; B05D007-14; B05D007-24
		IPCI	B01J0035-02 [ICM,6]; B05D0001-38 [ICS,6]; B05D0007-14 [ICS,6]; B05D0007-24 [ICS,6]
		IPCR	B01J0035-00 [I,C*]; B01J0035-02 [I,A]; B05D0001-38 [I,A]; B05D0001-38 [I,C*]; B05D0005-00 [I,A]; B05D0005-00 [I,C*]; B05D0007-14 [I,A]; B05D0007-14 [I,C*]; B05D0007-24 [I,A]; B05D0007-24 [I,C*]

AB The coatings comprise, from the substrate surface, a Zn-rich paint, a synthetic resin base coating, an intermediate coating containing hydrolyzable silyl group-containing vinyl polymers (I), hydrolyzed organosilanes (II) or their partially condensates and pigments, and a top coating containing I, II or solvent-soluble fluoropolymers, and TiO₂ photocatalysts in an amount so that the PWC (pigment weight concentration) reaches 45-85%.

The coatings show high NO_x-removing activity and excellent antifouling property. Thus, an intermediate coating was obtained from a 55%-solids copolymer of iso-Bu methacrylate, 2-ethylhexyl methacrylate and CH₂:CMeCO₂(CH₂)₃Si(OMe)₃, 100, TiO₂ 25, CaCO₃ 15, BaSO₄ 10 parts and Bu₂Sn laurate. A top coating was obtained from a hydrolytic polycondensate of MeSi(OEt)₄ 100, SSP 25 (photocatalyst TiO₂) 160, xylol 10, iso-Pr alc. 10 parts, and Bu₂Sn laurate. Coating pre-blasted steel plate with a Zn-rich paint (Zn concentration 70%), a basecoat containing Epikote 828-Tohmide 245 copolymer, the intermediate coating, and the top coating gave a coated steel showing good resistance to salt spray and weather and NO_x-removing ability.

ST anticorrosive coating nitrogen oxide removal activity; photocatalyst titania multilayer antifouling coating;

- acrylic alkoxy silane condensate anticorrosive antifouling coating; zinc rich multilayer anticorrosive antifouling coating; metal anticorrosive coating photocatalyst titania pigment
- IT Corrosion prevention
Photolysis catalysts
(NOx-removing multilayer anticorrosive antifouling coatings for metal surface)
- IT Polysiloxanes, uses
RL: IMF (Industrial manufacture); POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(acrylic, intermediate coating; NOx-removing multilayer anticorrosive antifouling coatings for metal surface)
- IT Coating materials
Coating materials
(anticorrosive, weather-resistant, antifouling; NOx-removing multilayer anticorrosive antifouling coatings for metal surface)
- IT Coating materials
(antifouling, anticorrosive, weather-resistant; NOx-removing multilayer anticorrosive antifouling coatings for metal surface)
- IT Epoxy resins, uses
RL: IMF (Industrial manufacture); POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(base coatings; NOx-removing multilayer anticorrosive antifouling coatings for metal surface)
- IT Acrylic polymers, uses
Chlorinated natural rubber
Phenolic resins, uses
RL: POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
(basecoat; NOx-removing multilayer anticorrosive antifouling coatings for metal surface)
- IT Polyesters, uses
RL: PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
(basecoat; NOx-removing multilayer anticorrosive antifouling coatings for metal surface)
- IT Soybean oil
RL: POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
(reaction products with alkyd resins, basecoat; NOx-removing multilayer anticorrosive antifouling coatings for metal surface)
- IT Alkyd resins
RL: POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
(soybean oil-modified, basecoat; NOx-removing multilayer anticorrosive antifouling coatings for metal surface)
- IT Fluoropolymers, uses
Silsesquioxanes
RL: IMF (Industrial manufacture); POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(topcoat; NOx-removing multilayer anticorrosive antifouling coatings for metal surface)
- IT 11104-93-1, NOx, miscellaneous
RL: MSC (Miscellaneous)
(NOx-removing multilayer anticorrosive antifouling coatings for metal surface)
- IT 90398-42-8P, Bisphenol A-epichlorohydrin-Tohmide 245 copolymer
RL: IMF (Industrial manufacture); POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(base coatings; NOx-removing multilayer anticorrosive antifouling coatings for metal surface)

IT 9003-22-9
RL: POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
(basecoat Vinylite VYHH (a vinyl chloride copolymer); NOx-removing multilayer anticorrosive antifouling coatings for metal surface)

IT 110-63-4DP, Butylene glycol, polyesters with adipic acid, triol, phthalic acid and trimethylolpropane, crosslinked with polyisocyanate
124-04-9DP, Adipic acid, polyesters with butylene glycol, triol, phthalic acid and trimethylolpropane, crosslinked with polyisocyanate
108362-54-5P, Adipic acid-butylene glycol-Desmophen 1100-Mitec GP
101A-phthalic acid-trimethylolpropane copolymer
RL: IMF (Industrial manufacture); POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(basecoat; NOx-removing multilayer anticorrosive antifouling coatings for metal surface)

IT 70535-97-6, Hitanol 1131 97047-43-3, Acrydic A 169
RL: POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
(basecoat; NOx-removing multilayer anticorrosive antifouling coatings for metal surface)

IT 217945-76-1P, Isobutyl methacrylate-2-ethylhexyl methacrylate- γ -methacryloxypropyltrimethoxysilane copolymer
RL: IMF (Industrial manufacture); POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(intermediate coating; NOx-removing multilayer anticorrosive antifouling coatings for metal surface)

IT 13463-67-7, Titania, uses
RL: CAT (Catalyst use); USES (Uses)
(photocatalyst/pigment; NOx-removing multilayer anticorrosive antifouling coatings for metal surface)

IT 12732-02-4, SS 400, uses
RL: PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
(substrate; NOx-removing multilayer anticorrosive antifouling coatings for metal surface)

IT 25930-91-0P, Methyltriethoxysilane homopolymer 151755-31-6P, Coronate HX-Lumiflon LF 200 copolymer 153315-80-1P, Methyltriethoxysilane homopolymer, ladder SRU
RL: IMF (Industrial manufacture); POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(topcoat; NOx-removing multilayer anticorrosive antifouling coatings for metal surface)

IT 11099-06-2, Ethyl Silicate 40
RL: PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
(topcoat; NOx-removing multilayer anticorrosive antifouling coatings for metal surface)

IT 7440-66-6, Zinc, uses
RL: PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
(undercoatings; NOx-removing multilayer anticorrosive antifouling coatings for metal surface)

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FILE 'CAPLUS' ENTERED AT 10:10:24 ON 11 JAN 2008

L1 9191 S ANTIFOUL? OR ANTI ADJ FOUL?
L2 463 S L1 AND PHOTO?
L3 72 S L2 AND (FLUORO? OR PERFLUORO? OR DIFLUOR? OR TRIFLUOR? OR TET
L4 1 S L3 AND (METHYLOL? OR DIMETHYLOL? OR TRIMETHYLOL? OR TETRAMETH

=> s 13 and cymel
3290 CYMEL
L5 1 L3 AND CYMEL

=> s 15 not 14
L6 1 L5 NOT L4

=> d all

L6 ANSWER 1 OF 1 CAPLUS COPYRIGHT 2008 ACS on STN
AN 2001:581572 CAPLUS
DN 135:159174
ED Entered STN: 10 Aug 2001
TI Radiographic image converter panel
IN Ogawa, Hiroshi
PA Fuji Photo Film Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 18 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM G21K004-00
CC 71-7 (Nuclear Technology)
Section cross-reference(s): 38, 63, 74

FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 2001215299	A	20010810	JP 2000-22358	20000131
PRAI JP 2000-22358			20000131	

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 2001215299	ICM	G21K004-00
	IPCI	G21K0004-00 [ICM, 7]
	IPCR	G21K0004-00 [I, C*]; G21K0004-00 [I, A]

AB The invention relates to a radiog. image converter panel comprising a photostimulable phosphor-containing layer, wherein the protective layer is made of the polysiloxane segment-containing fluoropolymer in which the fluorine content is $\geq 30\%$ and the polystyrene-based number average mol. weight is ≥ 5000 , for enhancing the scratch prevention and antifouling properties.

ST radiog image converter panel polysiloxane fluoropolymer

IT Aminoplasts

RL: MOA (Modifier or additive use); USES (Uses)
(crosslinking agent; radiog. image converter panel)

IT Phosphors
(photostimulable; radiog. image converter panel)

IT Radiation detectors
X-ray detectors
(radiog. image converter panel)

IT Fluoropolymers, uses
Polysiloxanes, uses
RL: DEV (Device component use); USES (Uses)
(radiog. image converter panel)

IT Aminoplasts
RL: MOA (Modifier or additive use); USES (Uses)
(radiog. image converter panel)

IT Emulsifying agents
(reactive; radiog. image converter panel)

IT Optical imaging devices
(x-ray converters; radiog. image converter panel)

IT 9003-08-1, Cymel 303 15968-37-3, Cymel 1170
 164325-70-6, Mycoat 106
 RL: MOA (Modifier or additive use); USES (Uses)
 (crosslinking agent; radiog. image converter panel)
 IT 158947-07-0, VPS 1001
 RL: CAT (Catalyst use); USES (Uses)
 (radiog. image converter panel)
 IT 248949-40-8P 248949-48-6P 248949-52-2P 352430-40-1P 352430-42-3P
 352430-45-6P
 RL: DEV (Device component use); IMF (Industrial manufacture); PREP
 (Preparation); USES (Uses)
 (radiog. image converter panel)
 IT 16910-54-6, Europium ion(2+), uses 112286-11-0, Barium bromide fluoride
 iodide (BaBr_{0.85}FI_{0.15})
 RL: MOA (Modifier or additive use); USES (Uses)
 (radiog. image converter panel)

=> s 9003-08-1/rn and 13
 19726 9003-08-1
 1877 9003-08-1D
 18003 9003-08-1/RN
 (9003-08-1 (NOTL) 9003-08-1D)

L7 3 9003-08-1/RN AND L3

=> s 17 not 16
 L8 2 L7 NOT L6

=> d all 1-3

L8 ANSWER 1 OF 2 CAPLUS COPYRIGHT 2008 ACS on STN
 AN 2000:762039 CAPLUS
 DN 133:323087
 ED Entered STN: 31 Oct 2000
 TI Antifouling and antisoiling coating compositions
 IN Watanabe, Yutaka; Murawaki, Toshihiro; Kitamura, Toru
 PA Nippon Biso K. K., Japan; Toho Kengyo K. K.
 SO Jpn. Kokai Tokkyo Koho, 4 pp.
 CODEN: JKXXAF
 DT Patent
 LA Japanese
 IC ICM C09D005-16
 ICS C09D005-00; C09D183-04; C09D201-00
 CC 42-10 (Coatings, Inks, and Related Products)
 Section cross-reference(s): 5

FAN.CNT 1	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 2000303004	A	20001031	JP 1999-114704		19990422
PRAI JP 1999-114704			19990422		

CLASS	PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
JP 2000303004	ICM	C09D005-16	
	ICS	C09D005-00; C09D183-04; C09D201-00	
	IPCI	C09D0005-16 [ICM,7]; C09D0005-00 [ICS,7]; C09D0183-04 [ICS,7]; C09D0201-00 [ICS,7]	
	IPCR	C09D0005-16 [I,C*]; C09D0005-16 [I,A]; C09D0005-00 [I,C*]; C09D0005-00 [I,A]; C09D0183-04 [I,C*]; C09D0183-04 [I,A]; C09D0201-00 [I,C*]; C09D0201-00 [I,A]	

AB Title compns. contain anatase TiO₂ pigments, (organosiloxanes, and organic resins as major components at a preferable TiO₂/siloxane of 20-300%. A typical composition comprised ST 01 20, KC 89 60, Fluonate K 704 120, Bu₂Sn dilaurate 0.001, xylene 20, PhMe 20, and Burnock DN 980S 15 g.

ST antifouling antisoiling coating photocatalyst titania
 siloxane polymeric binder
 IT Polysiloxanes, uses
 RL: MOA (Modifier or additive use); POF (Polymer in formulation); USES (Uses)
 (KC 89; photocatalytic TiO₂- and siloxane-containing polymer
 binder coatings with antisoiling and antifouling ability)
 IT Coating materials
 (antisoiling; photocatalytic TiO₂- and siloxane-containing
 polymer binder coatings with antisoiling and antifouling
 ability)
 IT Antifouling agents
 (photocatalytic TiO₂- and siloxane-containing polymer binder
 coatings with antisoiling and antifouling ability)
 IT Acrylic polymers, uses
 Aminoplasts
 Fluoropolymers, uses
 Polyamides, uses
 Polyesters, uses
 Polyurethanes, uses
 RL: POF (Polymer in formulation); TEM (Technical or engineered material
 use); USES (Uses)
 (photocatalytic TiO₂- and siloxane-containing polymer binder
 coatings with antisoiling and antifouling ability)
 IT 249288-32-2P, Burnock DN 980S-Fluonate K 704 copolymer
 RL: IMF (Industrial manufacture); POF (Polymer in formulation); TEM
 (Technical or engineered material use); PREP (Preparation); USES (Uses)
 (photocatalytic TiO₂- and siloxane-containing polymer binder
 coatings with antisoiling and antifouling ability)
 IT 13463-67-7, ST 01, uses
 RL: MOA (Modifier or additive use); USES (Uses)
 (photocatalytic TiO₂- and siloxane-containing polymer binder
 coatings with antisoiling and antifouling ability)
 IT 9002-86-2, PVC 9003-08-1, Melamine resin
 RL: POF (Polymer in formulation); TEM (Technical or engineered material
 use); USES (Uses)
 (photocatalytic TiO₂- and siloxane-containing polymer binder
 coatings with antisoiling and antifouling ability)

L8 ANSWER 2 OF 2 CAPLUS COPYRIGHT 2008 ACS on STN
 AN 1998:640312 CAPLUS
 DN 129:261828
 ED Entered STN: 09 Oct 1998
 TI Antifouling silicone emulsion coating compositions, manufacture
 thereof and antifouling articles coated therewith
 IN Takahama, Koichi; Yamaki, Takeyuki; Inoue, Minoru; Goto, Akiharu; Ikenaga,
 Junko; Kishimoto, Hirotugu
 PA Matsushita Electric Works, Ltd., Japan
 SO PCT Int. Appl., 86 pp.
 CODEN: PIXXD2
 DT Patent
 LA Japanese
 IC ICM C09D183-06
 ICS C08L083-06; C08K003-22
 CC 42-10 (Coatings, Inks, and Related Products)
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	WO 9841589	A1	19980924	WO 1998-JP1071	19980313
	W: CA, KR, US				
	RW: AT, BE, CH, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE				
JP	10316937	A	19981202	JP 1998-58665	19980310
JP	2920140	B2	19990719		
CA	2253504	A1	19980924	CA 1998-2253504	19980313
CA	2253504	C	20021119		

EP 942052	A1	19990915	EP 1998-907224	19980313
EP 942052	B1	20060705		
R: BE, CH, DE, ES, FR, GB, IT, LI, NL, SE				
KR 2000011140	A	20000225	KR 1998-709300	19981114
US 6221498	B1	20010424	US 1999-180763	19990111
PRAI JP 1997-61573	A	19970314		
WO 1998-JP1071	W	19980313		
CLASS				
PATENT NO. CLASS PATENT FAMILY CLASSIFICATION CODES				
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WO 9841589	ICM	C09D183-06		
	ICS	C08L083-06; C08K003-22		
	IPCI	C09D0183-06 [ICM, 6]; C08L0083-06 [ICS, 6]; C08L0083-00 [ICS, 6, C*]; C08K0003-22 [ICS, 6]; C08K0003-00 [ICS, 6, C*]		
	IPCR	C08K0003-00 [I, C*]; C08K0003-22 [I, A]; C09D0183-04 [I, C*]; C09D0183-04 [I, A]		
	ECLA	C08K003/22+L83/04; C09D183/04+F		
JP 10316937	IPCI	C09D0183-06 [ICM, 6]; C09D0005-16 [ICS, 6]; C09D0007-12 [ICS, 6]; C09D0115-02 [ICS, 6]; C09D0115-00 [ICS, 6, C*]; C09D0127-12 [ICS, 6]; C09D0133-08 [ICS, 6]; C09D0161-06 [ICS, 6]; C09D0161-00 [ICS, 6, C*]; C09D0161-28 [ICS, 6]; C09D0161-20 [ICS, 6, C*]; C09D0163-00 [ICS, 6]; C09D0167-02 [ICS, 6]; C09D0167-08 [ICS, 6]; C09D0175-04 [ICS, 6]		
	IPCR	C09D0005-16 [I, A]; C09D0005-16 [I, C*]; C09D0007-12 [I, A]; C09D0007-12 [I, C*]; C09D0115-00 [I, C*]; C09D0115-02 [I, A]; C09D0127-12 [I, A]; C09D0127-12 [I, C*]; C09D0133-08 [I, A]; C09D0133-08 [I, C*]; C09D0161-00 [I, C*]; C09D0161-06 [I, A]; C09D0161-20 [I, C*]; C09D0161-28 [I, A]; C09D0163-00 [I, A]; C09D0163-00 [I, C*]; C09D0167-02 [I, A]; C09D0167-02 [I, C*]; C09D0167-08 [I, A]; C09D0167-08 [I, C*]; C09D0175-04 [I, A]; C09D0175-04 [I, C*]; C09D0183-06 [I, A]; C09D0183-06 [I, C*]		
CA 2253504	IPCI	C09D0183-06 [ICM, 6]; C09D0007-12 [ICS, 6]; C09D0005-16 [ICS, 6]		
	IPCR	C08K0003-00 [I, C*]; C08K0003-22 [I, A]; C09D0183-04 [I, C*]; C09D0183-04 [I, A]		
EP 942052	IPCI	C08K0003-00 [I, C]; C08L0083-00 [I, C]; C09D0183-06 [I, C]; C09D0183-06 [I, A]; C08K0003-22 [I, A]; C08L0083-06 [I, A]		
	IPCR	C08K0003-00 [I, C*]; C08K0003-22 [I, A]; C09D0183-04 [I, C*]; C09D0183-04 [I, A]		
	ECLA	C08K003/22+L83/04; C09D183/04+F		
KR 2000011140	IPCI	C09D0183-06 [ICM, 7]; C08K0003-22 [ICS, 7]; C08K0003-00 [ICS, 7, C*]; C08L0083-06 [ICS, 7]; C08L0083-00 [ICS, 7, C*]		
	IPCR	C08K0003-00 [I, C*]; C08K0003-22 [I, A]; C09D0183-04 [I, C*]; C09D0183-04 [I, A]		
	ECLA	C08K003/22+L83/04; C09D183/04+F		
US 6221498	IPCI	B32B0009-04 [ICM, 7]		
	IPCR	C08K0003-00 [I, C*]; C08K0003-22 [I, A]; C09D0183-04 [I, C*]; C09D0183-04 [I, A]		
	NCL	428/447.000; 106/287.120; 428/450.000; 428/451.000; 524/413.000; 524/497.000; 524/588.000; 524/837.000; 524/839.000; 525/902.000		
	ECLA	C08K003/22+L83/04; C09D183/04+F		

AB The title compns. comprise the following components (A)-(D), with the C content 5-80% based on overall solids in the composition: (A) a partial hydrolyzate of average composition formula R₂aSiOb(OR₁)c(OH)_d (R₁, R₂ = hydrocarbyl; a, b, c, d = nos. satisfying a + 2b + c + d = 4, 0 ≤ a < 3; 0 < b < 2; 0 < c < 4; 0 < d < 4) and having Mw 600-5,000 (polystyrene-equivalent), (B) a nonionic surfactant or an anionic surfactant, (C) a photosemiconductor, and (D) water. A reactive terminal silanol group-containing polysiloxane 50% solution in toluene was prepared from methyltrichlorosilane 44.8, dimethyldichlorosilane 38.7, and

phenyltrichlorosilane 84.6 parts, and the solution (100 parts) was mixed with 5 parts methyltrimethoxysilane and 5 parts dimethyldimethoxysilane and treated dropwise under stirring at 60° with a solution from 0.6 part dibutyltin dilaurate and 10 parts toluene, further stirred for 40 min, and concentrated to obtain a 80%-solids solution of desired partial hydrolyzate of

Mw 2000. The above solution (50 parts) was treated with 2 parts polyethylene glycol nonylphenyl ether as polymerization initiator, concentrated in vacuo under

stirring, stirred with 5 parts polyethylene glycol nonylphenyl ether, stirred with 290 parts water, homogenized, and mixed with 10 parts titania aqueous dispersion to obtain a coating composition

ST polysiloxane silsesquioxane antifouling coating titania photosemiconductor

IT Polysiloxanes, uses
RL: POF (Polymer in formulation); TEM (Technical or engineered material use); USES (Uses)
(acrylic; antifouling silicone emulsion coating compns., manufacture thereof and antifouling articles coated therewith)

IT Photoconductors
Surfactants
(antifouling silicone emulsion coating compns., manufacture thereof and antifouling articles coated therewith)

IT Acrylic polymers, uses
Alkyd resins
Aminoplasts
Chlorinated natural rubber
Epoxy resins, uses
Fluoropolymers, uses
Phenolic resins, uses
Polyesters, uses
Polysiloxanes, uses
Polyurethanes, uses
RL: POF (Polymer in formulation); TEM (Technical or engineered material use); USES (Uses)
(antifouling silicone emulsion coating compns., manufacture thereof and antifouling articles coated therewith)

IT Coating materials
(antifouling; antifouling silicone emulsion coating compns., manufacture thereof and antifouling articles coated therewith)

IT 25498-03-7P, Methyltrimethoxysilane homopolymer 111740-14-8P, Butyl methacrylate-trimethoxysilylpropyl methacrylate-glycidyl methacrylate copolymer 153315-80-1P, Methyltrimethoxysilane homopolymer, ladder sru 156940-48-6P, Methyltrimethoxysilane-dimethyldimethoxysilane-tetraethoxysilane copolymer 209261-07-4P, Methyltrichlorosilane-dimethyldichlorosilane-phenyltrichlorosilane-methyltrimethoxysilane-dimethyldimethoxysilane copolymer
RL: IMF (Industrial manufacture); POF (Polymer in formulation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(antifouling silicone emulsion coating compns., manufacture thereof and antifouling articles coated therewith)

IT 9016-45-9, Polyethylene glycol nonylphenyl ether 13463-67-7, STS 01, uses 25155-30-0, Sodium dodecylbenzenesulfonate
RL: MOA (Modifier or additive use); USES (Uses)
(antifouling silicone emulsion coating compns., manufacture thereof and antifouling articles coated therewith)

IT 9003-08-1, Melamine resin 9005-12-3, Methylphenylsilanediol homopolymer, sru 9016-00-6, Dimethylsilanediol homopolymer, sru 31230-04-3, Methylphenylsilanediol homopolymer 31900-57-9, Dimethylsilanediol homopolymer
RL: POF (Polymer in formulation); TEM (Technical or engineered material use); USES (Uses)
(antifouling silicone emulsion coating compns., manufacture thereof and antifouling articles coated therewith)

RE.CNT 1 THERE ARE 1 CITED REFERENCES AVAILABLE FOR THIS RECORD

RE

(1) Giken Kogyo Corp; JP 6183106 A 1986

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FILE 'CAPLUS' ENTERED AT 10:10:24 ON 11 JAN 2008

L1 9191 S ANTIFOUL? OR ANTI ADJ FOUL?
L2 463 S L1 AND PHOTO?
L3 72 S L2 AND (FLUORO? OR PERFLUORO? OR DIFLUOR? OR TRIFLUOR? OR TET
L4 1 S L3 AND (METHYLOL? OR DIMETHYLOL? OR TRIMETHYLOL? OR TETRAMETH
L5 1 S L3 AND CYMEL
L6 1 S L5 NOT L4
L7 3 S 9003-08-1/RN AND L3
L8 2 S L7 NOT L6

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